

# Ion Implantation Technology 2010: 18th International Conference On Ion Implantation Technology, IIT 2010, Kyoto, Japan, 6-11 June 2010

## by International Conference on Ion Implantation Technology ; Jiro Matsuo

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18th International Conference on Ion Implantation Technology. IIT 2010. Kyoto, Japan 6-11 June 2010. EDITORS. Jiro Matsuo. Kyoto University Japan. Mar 8 - Hesburgh Libraries - University of Notre Dame 2011?1?24? . ???ION Implantation Technology 2010: 18th International Conference on Ion Implantation Technology IIT 2010, Kyoto, Japan 6-11 June? 11 Jun 2011 . ion implantation technology 2010,18th international conference on ion implantation technology iit 2010, kyoto, japan 6-11 june 2011. Publications - University of Glasgow The International Conference on Ion Implantation Technology (IIT) is biannual international . The 18th IIT conference will be held in June 2010, at Kyoto - the center of Japanese tradition and history, and also June 6-11, 2010, Kyoto University Clock Tower Centennial Hall, Kyoto, Gokasho, Uji, Kyoto, 611-0011 Japan LaTeX Original - Atomki B. 2010, V.81, 113303; ??.????????, ??.??????, ??. ???????? 18th International Symposium Nanostructures: Physics and technology, ion irradiation XI International conference and seminar EDM 2010, June 30- July 4, Erlagol, p. of Ion Implantation Technology (IIT 2010), Jun 6-11, 2010, Kyoto, Japan, P2-45 ION Implantation Technology 2010: 18th International Conference . 2014; 2013; 2012; 2011; 2010; 2009 . Workshop on Computational Electronics (IWCE), Paris, France , 3-6 June 2014, pp. 1-4. .. Optics Express, 22(18), pp. In: The 20th International Conference on Ion Implantation Technology (IIT 2014), Processes and Devices (SISPAD) , Yokohama Japan, 8-11 Sep 2014, pp. Ion Implantation Technology 2010: 18th International Conference . 18th International Conference on Ion Implantation Technology (Kyoto. University, Japan, 2010/6/9, Oral). 70. T. Aoki, "Damage and sputtering with cluster impact ION Implantation Technology 2010 - Jiro (EDT) Matsuo, Masataka . June3-5, 2010. Place. Miyako Messe (Kyoto International Exhibition Hall). Textbook On-line registration is also available for IIT School as Masataka Kase (Japan) IIT2010. 18th International Conference on. Ion Implantation Technology. June 6?11 IIT School. June 6-11, 2010. IIT2010 Conference. Registration Fee.

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